

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>				Docket Number (Optional) <b>72478-3400</b>		Application Number <b>09/997,988</b>		
				Applicant(s) <b>Masaki Aoki et al.</b>				
				Filing Date <b>November 29, 2001</b>		Group Art Unit <b>1722</b>		
<b>U. S. PATENT DOCUMENTS</b>								
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
		<b>4,717,584</b>	<b>1.5.1988</b>	<b>Aoki et al.</b>				
		<b>4,926,095</b>	<b>5.15.1990</b>	<b>Shinoda et al.</b>				
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>								
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<b>FOREIGN PATENT DOCUMENTS</b>								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
		<b>61-287032</b>	<b>12.17.1986</b>	<b>Japan (See USP 4,717,584)</b>			<b>X</b>	
		<b>2001-104774</b>	<b>4.17.2001</b>	<b>Japan w/English Abstract</b>			<b>X</b>	
		<b>2004-170394</b>	<b>6.17.2004</b>	<b>Japan w/English Abstract</b>			<b>X</b>	
		<b>90-008640</b>	<b>11.26.1990</b>	<b>Korea (See USP 4,926,095)</b>			<b>X</b>	
<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
		<b>Fujii, E. et al, "NaCl-type Oxide Films Prepared by Plasma-Enhanced Metalorganic Chemical Vapor Deposition", Japanese Journal of Applied Physics, Part 2 (letters), Vol. 32, No. 10A, L1448-L1450, October. 1, 1993.</b>						
EXAMINER				DATE CONSIDERED				
<b>EXAMINER:</b> Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								